

[ABSTRACT]

Disclosed is a polishing pad including a polishing layer that is a molded body of a polyurethane composition, wherein the polyurethane composition contains 90 to 99.9 mass% of a thermoplastic polyurethane including a non-alicyclic diisocyanate unit as an organic diisocyanate unit, and 0.1 to 10 mass% of a hygroscopic polymer, and the molded body has a hardness of 75 to 90, as measured with a type-D durometer compliant with JIS K 7215.